

# 3kW System Microwave Plasma CVD

## Model and Supplier: N.A. (Handmade Equipment)

Low cost manually controlled system with 1" deposition area

- Easy to use and small in size
- Quartz bell jar chamber
- Reactor Kit available (for user custom integration)
- Heater kit (optional with up to 850C max. temperature)
- Operating Pressure range: 10-50Torr

## Applications

- ◆ Conventional and Doped Micro-crystalline Diamond (2" diameter)
- ◆ Nano and Ultra Nano-crystalline Diamond (2-3" diameter)
- ◆ Carbon Nano-tubes (2-3" High Growth Rate and Device Quality)
- ◆ Single Crystal Diamond (High Growth Rate and Device Quality)
- ◆ Hetero-epitaxial Diamond (with DC biasing)